



Position Description

College / Division:	College of Science
School / Centre:	Research School of Physics and Engineering (RSPE)
Department / Unit:	EME/ACT Node of ANFF
Position Title:	Senior Technical Officer (Electron Beam Lithography)
Classification:	ANU Officer Grade 7 (Research)
Position No:	16644
Responsible to:	Node Manager, ACT Node of ANFF

PURPOSE STATEMENT:

The Australian National Fabrication Facility (ANFF) ACT Node, hosted at the Research School of Physics and Engineering – ANU, provides Australian researchers with state-of-the-art micro- and nano-fabrication capabilities in the fields of, but not limited to, semiconductor materials and devices for opto-electronic applications, nano-photonics, photovoltaics, etc.

The Senior Technical Officer (Electron Beam Lithography) will provide an efficient management and operation of the node EBL system which is an ANFF flagship equipment. In addition the Senior Technical Officer (EBL) will carry out various lithography processes, train and supervise users of the system, in support of their research programs. The position may be required to help with other ANFF equipment.

KEY ACCOUNTABILITY AREAS:

Position Dimension & Relationships:

The Senior Technical Officer (Electron Beam Lithography) is based at the Research School of Physics and Engineering. The Officer will work closely with a broad range of people who are directly or indirectly involved in ANFF. He/she will also be required to interact with academics, students and staff from both ANU and other Australian Institutions who would be accessing the node and its EBL system.

Role Statement:

Under the broad direction of the Node Manager, the Senior Technical Officer (Electron Beam Lithography) will:

1. Maintain the efficient operation and usage of the ANFF-designated electron beam lithography (EBL) system - including preventive maintenance, repair, service and daily operation of the system.
2. Instruct, train and supervise staff and students from ANU and other Australian institutions in the use of the EBL system.
3. Carry out various lithography processes as required by the users of the EBL system, in consultation with the node manager.
4. Develop new and innovative lithography processes/recipes with regards to the EBL system.
5. Maintain accurate documentation concerning the EBL system, such as facility usage, operational costs and other management records including occupational health and safety issues.
6. Assist other ANFF staff with tasks on other ANFF equipment.
7. Comply with all ANU policies and procedures, in particular those relating to work health and safety and equal opportunity.
8. Other duties as consistent with the classification of the position.

SELECTION CRITERIA:

1. Completion of a degree with relevant work experience or an equivalent combination of relevant experience and/or education and training.
2. Excellent expertise in Electron Beam Lithography systems and experience in semiconductor/wafer processing, specifically in lithography.
3. Experience with other thin film processing equipment such as plasma etching and deposition, optical lithography, and metrology tools.
4. Extensive experience in the instruction, training and supervision of staff and/or students in the use of scientific research equipment.
5. Highly developed interpersonal and communication skills, both written and verbal, including the ability to consult, negotiate and liaise effectively with a diverse range of stakeholders both internal and external to the University.
6. Proven ability to work efficiently, to establish priorities, meet deadlines and to effectively contribute as a member of a small team.
7. A demonstrated understanding of equal opportunity principles and policies and a commitment to their application in a university context.

Delegate Signature:		Date:	12-04-2018
Printed Name:	Dr. Fouad Karouta	Uni ID:	U4703981

References:
[General Staff Classification Descriptors](#)
[Academic Minimum Standards](#)